

<b>Form 1449 (Modified)</b>  <b>Information Disclosure Statement By Applicant</b>  (Use Several Sheets if Necessary)	Atty Docket No.	Application No.:
	LSIIP239/03-1810	Not yet assigned
	Applicant:	
	Eib et al.	
	Filing Date	Group
	Herewith	Not yet assigned

#### U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date

#### Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No

#### Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
DCD	A1	Shroff et al., "Optical Analysis of Mirror Based Pattern Generation", Emerging Lithographic Technologies VII, pp. 550-559. © 2003.
Examiner /Daborah Chacko-Davis/		Date Considered 06/02/2006

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.